



SFW

**PATENT APPLICATION**

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of

Jun HATAKEYAMA et al.

Group Art Unit: 1752

Application No.: 10/797,201

Examiner: R. SCHILLING

Filed: March 11, 2004

Docket No.: 118988

For: AN ANTI-REFLECTION FILM MATERIAL AND A SUBSTRATE HAVING AN  
ANTI-REFLECTION FILM AND A METHOD FOR FORMING A PATTERN

**AMENDMENT**

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Sir:

In reply to the February 21, 2006, Office Action, please consider the following:

**Amendments to the Claims** as reflected in the listing of claims; and

**Remarks.**